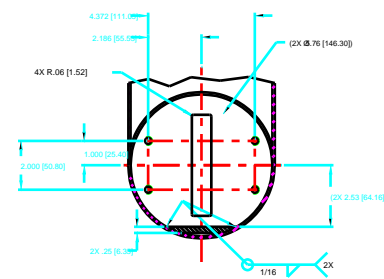
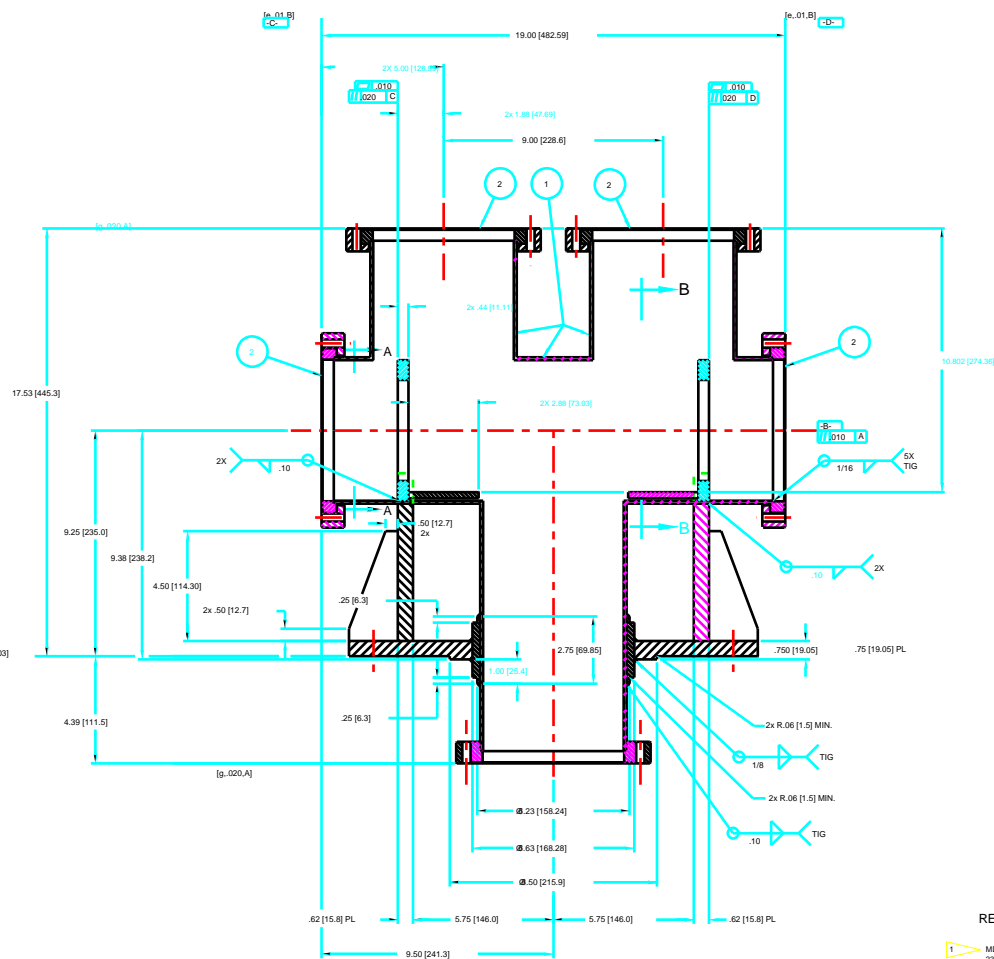


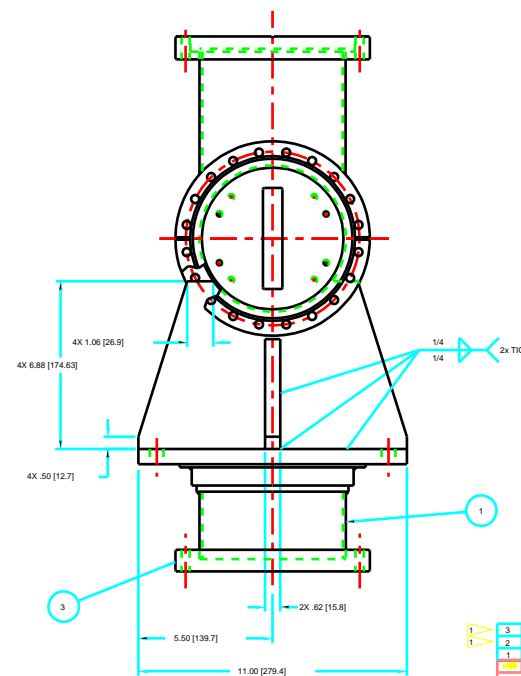
SECTION B-B



SECTION C-C



SECTION A-A



NOTES

2. THIS IS A ULTRA-HIGH VACUUM CHAMBER (UHV).
3. WHEN MACHINE VACUUM PARTS, USE OF SILICONE AND SULPHUR-BASED CUTTING FLUIDS IS PROHIBITED. USE ONE OF THE FOLLOWING:
  - a) CIMCOOL 5 STAR 49
  - b) TRIM SOL
4. ELECTROPOLISHING IS NEEDED BEFORE WELDING. PRIOR TO ELECTROPOLISHING, THE CHAMBER NEEDS TO GO THROUGH A MULTIPLE STEP CLEANING PROCESS INVOLVING DEGRASSING, WASHING AND DRYING. NITROGEN BLOW DOWN THE CHAMBER VACUUM SIDE SURFACE ROUGHNESS SHALL BE BETTER THAN 63 MICRONH RMS AFTER ELECTROPOLISHING.
5. WELD SHALL BE GAS TUNGSTEN ARC (GTAW) OR TUNGSTEN INERT GAS (TIG) VACUUM SIDE OF JOINTS.
6. VACUUM CHAMBER SHALL BE LEAK TESTED USING A MASS FLOW METER WITH TITANIUM SENSITIVE RANGE OF 2 x 10 STANDARD CC/SEC PER LEAK TESTER DIVISION, SUCH AS:
  - a) ALCATEL ASM-110TCL
  - b) VARIAN RSC 925 OR 936
  - c) VEECO MS-45, MS-40 OR MS-18
  - d) DUPONT CEC 24-1028
7. CALIBRATION OF THE LEAK DETECTOR SENSITIVITY SHALL BE PERFORMED JUST PRIOR TO TESTING.
8. THE CHAMBER WILL BE CONSIDERED PASSING THE CHAMBER (BAGGING) WITH HELIUM, THE CHAMBER WILL BE REJECTED IF A 2% DEFLECTION IN THE MOST SENSITIVE RANGE OF THE LEAK DETECTOR IS SENSED WITHIN 1 MIN.
9. ALL FLANGES ARE TO BE PERPENDICULAR TO TANK AXIS N/200.
10. ALL DIMENSIONS IN [ ] ARE MILLIMETERS AND ARE FOR REFERENCE ONLY.
11. MACHINE **PLAN** FOR ALL VACUUM SURFACE BEFORE ELECTROPOLISHING.
12. ALL MATERIAL IS 304 SS UNLESS OTHERWISE SPECIFIED.

#### REFERENCE SOURCE

1 MDC VACUUM PRODUCTS CORP  
23842 CABOT BOULEVARD  
HAYWARD, CA. 94545-1651  
(800)-443-8817

1	3	MDC #110031	FLANGE # N'OM. NONROTATABLE	SST 304	0
1	3	MDC #110031	FLANGE # N'OM. ROTATABLE	SST 304	0
1	1		TUBING 6.00 O.D. x 1.20 WALL	SST 304	0
<b>Notes:</b> <i>Original design</i> <i>See drawing for dimensions</i> <i>Part 2, L 151</i>			<b>Part 2, L 151</b> <i>See drawing for dimensions</i>		
<b>Part 1, L 150</b> <i>See drawing for dimensions</i> <b>P8610000-00</b> <b>MUSCIA</b> <b>12/17/8</b> <b>D.B.SHU</b> <b>1/27/98</b> <b>J.C.HANG</b> <b>1/23/98</b> <b>T.A.KLUZY</b> <b>2/5/98</b> <b>CHANG-MUSCIA</b> <b>12/17/8</b> <b>J.C.HANG</b> <b>1/23/98</b>			<b>Argonne NATIONAL LABORATORY</b> <b>ADVANCED PHOTON SOURCE</b> <b>P86-010</b> <b>MONO. INTEGRAL SHUTTER</b> <b>VACUUM CHAMBER WELDMT</b>		
<b>See PARTS LIST</b>			<b>Part 2, L 151</b> <b>E</b> <b>P8610000-00</b>		